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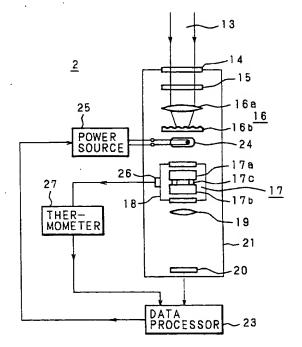
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(54) Wavelength measuring device and laser apparatus equipped with the device.

A wavelength measuring device (2) comprises a standard light source (24) which emits light of a predetermined wavelength and means for introducing light from a light source (24) to be measured into the device (2). The device further comprises a photosensor (20) and light from the light sources is directed onto the photosensor (20) via a Fabry-Perot etalon (17).

Means (23,26,27) are provided for correcting an error in the measured wavelength of the light to be measured on the basis of the deviation of a fringe formed by the light from the standard light source (24) on the photosensor (20) from a predetermined expected fringe.

Fig. 3



EP 0 570 243 A

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BACKGROUND OF THE INVENTION

Field of the Invention

This invention relates to a wavelength measuring device and a laser apparatus equipped with the wavelength measuring device for generating laser of constant wavelength.

Description of the Related Art

Fig. 1 illustrates a conventional laser apparatus, for xample, disclosed in the Japanese Patent Application Laid-Open No. 1-84681 (1989). In the drawing, references 1, 5 and 6 respectively denote a laser oscillator, a full reflection mirror and a partial reflection mirror disposed confronting the full reflection mirror 5 via the laser oscillator 1. A Fabry-Perot etalon (referred to as FP hereinafter) denoted by a reference number 7 is located between the laser oscillator 1 and the partial reflection mirror 6. The FP 7 is housed in a sealed container 8 filled with a gas. A volume increasing/decreasing means 9 by bellows is connected to the sealed container 8. The volume increasing/decreasing means 9 is driven by a servo mechanism 10. A laser beam 11 is oscillated by the laser oscillator 1, full reflecting mirror 5, partial reflecting mirror 6 and FP 7. A mirror 12 picks out a part of the laser beam 11, a sampling beam 13 to be measured. A wavelength measuring device 2 measures wavelength of the sampling beam 13.

The wavelength measuring device 2 consists of an interference filter 14 allowing only the sampling b am 13 to pass through, a light intensity adjusting filt r 15, an integrator 16 for dispersing the sampling b am 13, an air spaced FP 17 with a gap used as a monitor, a sealed container 18 in which the FP 17 is sealed, an image formation lens 19, a photosensor 20 of a one-dimensional image sensor to observe a fringe generated by the FP 17, an optical shielding box 21 for shutting off the outside light, a temperature regulator 22 for maintaining the FP 17 at a constant temperature, and a data processor 23 for analyzing the fringes observed by the photosensor 20. The output of the data processor 23 is inputted to the servo mechanism 10.

The operation will be depicted hereinafter. Wavelength of the laser beam 11 emitted from the laser oscillator 1 is selected by various kinds of elements in the oscillator 1. For example, the intrinsic width of oscillating wavelength of an excimer laser is several angstroms, but the width is reduced when spectral elements such as a prism, a grating, an FP or the like are installed in the oscillator. Moreover, if the spectral elements are properly adjusted, optional wavelength can b set within the width of the intrinsic oscillating wavelength. However, the selected wavelength is hard to be stabilized with high accuracy due to ther-

mal deformation or vibration of the oscillator. As such, wavelength of the laser is measured by introducing the sampling beam 13, a part of the laser beam 11, into the wavelength measuring device 2, and driving the servo mechanism 10 based on the measuring result to change the pressure of the ambience gas in the FP 7, thus stabilizing the wavelength of the laser.

The wavelength measuring device 2 uses the FP 17 for determining the wavelength. The FP 17 called as an air spaced Fabry-Perot etalon is obtained by bonding two highly flat mirrors 17a, 17b sandwiching a spacer 17c of thickness d. The center wavelength of the light passing through the mirrors 17a, 17b at an angle θ is represented by an equation (1) below:

 $\lambda = 2nd \times cos\theta_m/m$ (1)

wherein n is a refractive index of the gap, m is an integer indicating the degree and $\theta_{\ m}$ is an angle of the degree m.

When the laser beam has a divergence angle after passing through the integrator, only the beam component satisfying the above equation (1) among the beams entered the FP 17 penetrates the FP 17, forming a coaxial fringe (a ring-shaped interference fringe) centering the optical axis of the laser beam at the focal of the image formation lens 19. As the photosensor 20 is arranged at the focal of the image formation lens 19, the waveform having the light intensity distribution as shown in Fig. 2 is obtained. The abscissa in Fig. 2 indicates a distance x from the center of the fringe. The peak position x_m of the fringe corresponding to the degree m is represented by the following equation (2):

$$x_m = f \times \theta_m$$
 (2)

Therefore, when the laser wavelength λ changes, the intensity distribution changes from that indicated by a solid line to that by a broken line in Fig. 2. The change of the laser beam in wavelength can be operated from the change of the peak positions x_m 's according to the equations (1) and (2).

As is understood from the equation (1), even when the wavelength λ does not change, θ_m changes by a change in n or d, and accordingly the peak position x_m of the fringes changes. In the conventional example, the FP 17 is sealed in the sealed container 18 and the density of the gas in the container 18 is kept constant so as to maintain the refractive index of the gap constant. Moreover, the temperature regulator keeps the temperature of the FP 17 constant so as to prevent the spacer 17c constituting the FP 17 from changing in thickness d of the spacer 17c as a result of thermal expansion.

When applying a KrF excimer laser as a light source of a lens reduction projection aligner in a semiconductor manufacturing apparatus, it is necessary to restrict the change of the laser wavelength not to exceed 0.5pm. Therefore, the allowable change $\Delta \, \lambda$ in wavelength to satisfy the measuring accuracy required for the wavelength measuring device 2 is ap-

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proximately 0.05pm. The spacer 17c of the FP 17 of the excimer laser is generally made of quartz glass having a thermal xpansion coefficient a of 5×10^{-7} . The change $\Delta\lambda$ in wavelength when the temperature of the spacer 17 changes by Δ T is expressed by an equation (3) :

$$\Delta \lambda = \lambda \times \Delta d/d = \lambda \times \alpha \times \Delta T \quad (3)$$

Accordingly, the temperature change of the spacer 17c should not exceed 0.4°C so as to restrict the change in wavelength not to exceed 0.05pm. In consequence, the temperature regulator 22 should restrict the temperature change of the FP 17 not to exceed 0.4°C.

Since the conventional wavelength measuring device and the wavelength stabilizing laser apparatus equipped with the wavelength measuring device are constructed to always necessitate the temperature regulator 22 in order to execute considerably minute control of the temperature, the conventional device and apparatus are disadvantageously complicated and expensive.

SUMMARY OF THE INVENTION

This invention has been devised to solve the aforementioned disadvantages, and has for its object to provide a wavelength measuring device capable of measuring wavelength with sufficiently high accuracy without using a temperature regulating means, and a wavelength stabilizing laser apparatus equipped with the wavelength measuring device.

The above and further objects and features of the invention will more fully be apparent from the following detailed description with accompanying drawings.

BRIEF DESCRIPTION OF THE DRAWINGS

Fig. 1 is a structural diagram of a conventional laser apparatus equipped with a wavelength measuring device;

Fig. 2 is a diagram of fringes formed on a photosensor of Fig. 1;

Fig. 3 is a structural diagram of a wavelength measuring device according to Embodiment 1 of this invention; and

Fig. 4 is a diagram of fringes formed on the photosensor of Fig. 3.

DESCRIPTION OF THE PREFERRED EMBODIMENTS

Embodiment 1

Fig. 3 shows the structure of a wavelength measuring device 2 according to Embodiment 1 of this invention when applying a KrF excimer laser. The same parts as those of the prior art are designated by the same reference numerals, and the description thereof will be abbreviated here. Referring to Fig. 3, a convex lens 16a and a scattering plate 16b constitute an integrator 16. After passing through the convex lens 16a and the scattering plate 16b, the beam having a divergence angle enters the FP 17.

A standard light source 24 is placed between the scattering plate 16b and the FP 17. In the embodiment, the standard light source 24 is a mercury lamp. A power source 25 for the standard light source 24 is turned ON/OFF by the data processor 23. To a temperature sensor 26 for measuring the temperature of the FP 17 is connected a temperature measuring device 27. The measured data by the temperature measuring device 27 is fed to the data processor 23.

Although a conventional temperature regulator is not employed in the embodiment, the measuring error caused by thermal expansion of the FP which changes a gap distance d can be predicted according to the equation (3) described earlier because the temperature of the FP 17 is measured. Accordingly, the correct wavelength is obtained by removing the measuring error predicted in accordance with the equation (3) from the actually measured wavelength which is calculated from the peak position of the fringe on the photosensor 20.

If the spacer 17c of the FP 17 is made of glass of such a linear expansion coefficient as 5x 10⁻⁷ or lower, the measuring error resulting from the temperature change naturally reduces much more.

Although it is possible to reduce the measuring error by using the special material, there actually exist errors relatively hard to be grasp by quantity, such as errors resulting from the change of the FP with time. Therefore, the arrangement in Fig. 3 using the standard light source 24 is devised to also eliminate such errors as above caused by intricate reasons, which enables more accurate measurement of the wavelength. The arrangement will be discussed more in detail below.

In Embodiment 1, the sampling beam 13 is a KrF excimer laser (wavelength $\lambda=248.4$ nm) and the standard light source 24 is a mercury lamp (wavelength $\lambda=252$ nm) close to that of a to-be-measured light. Fig. 4 shows both fringes formed by the mercury lamp and the KrF laser.

When measuring the peak position of the fringe by the mercury lamp for a long time while stopping the oscillation of the laser apparatus, although it is assumed that the peak position of the fringe does not change since wavelength of the mercury lamp does not change, the peak position of the fringe gradually changes in fact because of the changes with time of the glass material forming the FP 17 (change by the nm order of the gap d), or of the change in the refractive index n due to the leak of the filling gas or the gas emission through the material of the sealed container 18. Δ 0 HG is taken as an angle converted from the changing amount of the peak position, the equation

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(1) is differentiated to the following equation (4):

$$\Delta \lambda_{H_0}/\lambda_{H_0} = \Delta n_1/n + \Delta n_2/n + \Delta d_1/d + \Delta d_2/d + \tan\theta_{H_0} \times \Delta \theta_{H_0}$$
 (4)

wherein λ n_1 is the changing amount of the refractive index due to the change in the gas density, λ n_2 is the sum of the changing amounts of the refractive index except for λ n_1 , including, for example, the changing amount resulting from the gas emission via the composing material, λ d_1 is the changing amount of the gap d due to thermal expansion of the FP and λ d_2 is the changing amount of the gap d due to the change of the FP with time.

If a solid etalon or an air spaced Fabry-Perot etalon is used for the FP, Δ n_1 =0 is held by sealing the FP in a sealed container without leaking. Moreover, if the spacer 17c of the air spaced Fabry-Perot etalon is constituted of glass of a low expansion coefficient, or if the temperature of the FP is measured to correct the error, Δ d_1 =0 is satisfied.

Since the wavelength of the mercury lamp as a standard light source does not change, Δ λ $_{\text{Hg}}$ =0 is held. Accordingly, the following equation (5) is obtained:

 Δ n₂/n + Δ d₂/d = - tanθ _{Hg} × Δ θ _{Hg} (5) Thus, it becomes possible to predict the drift of the FP over a long term expressed by the terms on the right side of the equation (4) from the measuring value of Δ θ _{Hg}. In other words, a highly accurate measuring value of the wavelength is ensured when the measuring result is corrected by the amount of the drift.

Subsequently, by oscillating the laser apparatus whill stopping the mercury lamp, the angular change Δ θ is obtained from the change of the peak position of the fringe, and the changing amount Δ λ in wavelength of the laser beam is represented as follows:

$$\Delta \lambda \lambda \lambda = \Delta n_2 / n + \Delta d_2 / d + \tan \theta \times \Delta \theta = -\tan \theta$$

$$H_g \times \Delta \theta H_g + \tan \theta \times \Delta \theta$$
 (6)

The refore, in order to make the changing amount $\Delta \lambda$ in the wavelength of the laser beam equal to zero, the peak position of the fringe of the early laser beam before the longterm drift of the FP should be shifted by $\Delta \theta$ obtained in accordance with an equation (7) below. That is, the peak position should be corrected following the equation (7):

$$\Delta \theta = \tan \theta_{Hg} \times \Delta \theta_{Hg} / \tan \theta$$
 (7)

As depicted above, the wavelength measuring device of the embodiment removes the measuring error of the wavelength due to the temperature change of the FP 17 (Δ d₁=0) by measuring the temperature of the FP 17 by means of the temperature sensor 26. At the same time, the device corrects by shifting the peak position of the fringe formed by the laser beam by measuring the change of the peak position of the fringe formed by the standard light source 24. Therefore, the wavelength measuring device can obtain the considerably highly accurate result.

As explained with reference to Fig. 1, when the wavelength measuring device 2 is used in combina-

tion with the laser oscillator 1 and the measuring output signal is fed back to control the pressure of the ambience gas in the FP 7, a laser apparatus is capable of maintaining the wavelength of the laser beam constant for a long time.

Embodiment 2

Although the glass of low expansion coefficient forming the FP has a linear expansion coefficient of 5×10^{-7} or lower coefficient in the foregoing Embodiment 1, if a glass having the linear expansion coefficient of 0.5×10^{-7} or lower is used, the allowable temperature change of the FP so as to restrict the measuring error in wavelength of the KrF laser to 0.05pm is $\pm 4^{\circ}$ C. Therefore, since the temperature change in a general clean room is regulated within $\pm 2^{\circ}$ C, no particular consideration is needed for the circumstances where the wavelength measuring device or the laser apparatus equipped with the wavelength measuring device is installed.

Embodiment 3

The foregoing Embodiment 1 in which wavelength is corrected in use of the standard light source 24 is discussed on condition that $\Delta\,d_1$ is turned equal to 0 by forming the spacer 17c of the FP 17 of glass of a low linear expansion coefficient, or by measuring the temperature of the FP by the temperature sensor 26 for correction. The wavelength correcting method similar to the above without the above precondition, may be employed although the correcting amount enlarges and the same effect is achieved.

On the contrary, using a method to detect the temperature of the spacer alone for correction is possible.

As this invention may be embodied in several forms without departing from the spirit of essential characteristics thereof, the present embodiment is therefore illustrative and not restrictive, since the scope of the invention is defined by the appended claims rather than by the description preceding them, and all changes that fall within the metes and bounds of the claims, or equivalence of such metes and bounds thereof are therefore intended to be embraced by the claims.

Claims

 A device for measuring wavelength of a light by a fringe of the light formed on a photosensor via a Fabry-Perot etalon, comprising:

means for introducing a light source for emitting a to-be-measured light into the device;

a standard light source for emitting a light of predetermined wavelength; and

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means for correcting an error in the measured wavelength of the to-be-measured light on the basis of a deviation of a fringe formed by a light of the standard light source on the photosensor via the Fabry-Perot etalon from the fringe which should be formed by the light of the standard light source.

- A wavelength measuring device according to Claim 1, wherein a spacer between two mirrors of the Fabry-Perot etalon is made of glass having linear expansion coefficient of 5 x 10⁻⁷ or lower.
- A wavelength measuring device according to Claim 1, wherein the standard light source is a mercury lamp having wavelength close to that of the to-be-measured light.
- 4. A laser apparatus comprising:

a laser oscillator changeable of wavelength of oscillating laser;

the wavelength measuring device of Claim 1 for measuring wavelength of the laser from the laser oscillator; and

means for maintaining wavelength of the laser from the laser oscillator constant by controlling the wavelength of the laser from the oscillat r in accordance with an output signal from the wavelength measuring device.

- 5. A laser apparatus according to Claim 4, which is installed in a clean room.
- 6. A device for measuring wavelength of a light by a fringe of the light formed on a photosensor via a Fabry-Perot etalon, comprising:

means for detecting temperature of the Fabry-Perot etalon; and

means for correcting an error in the measured wavelength caused by thermal expansion of the Fabry-Perot etalon on the basis of a difference between the measured temperature and a stored reference temperature without thermal expansion of the Fabry-Perot etalon.

- 7. A wavelength measuring device according to Claim 6, wherein a spacer between two mirrors of the Fabry-Perot etalon is made of glass having linear expansion coefficient of 5 × 10-7 or lower.
- 8. A laser device comprising:

a laser oscillator changeable of wavelength of oscillating laser;

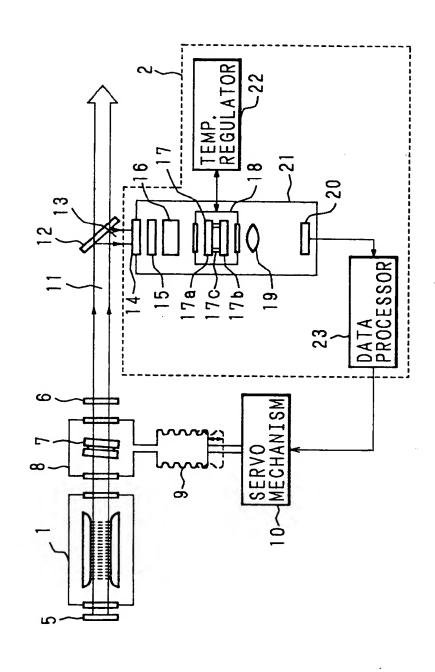
the wavelength measuring device of Claim 6 for measuring wavelength of the laser from the laser oscillator, and

means for maintaining wavelength of the laser from the laser oscillator constant by controlling the wavelength of the laser from the oscillator in accordance with an output signal from the wavelength measuring device.

- A laser device according to Claim 8, which is installed in a clean room.
- 10. A laser device substantially as herein described with reference to Figures 3 and 4 of the accompanying drawings.

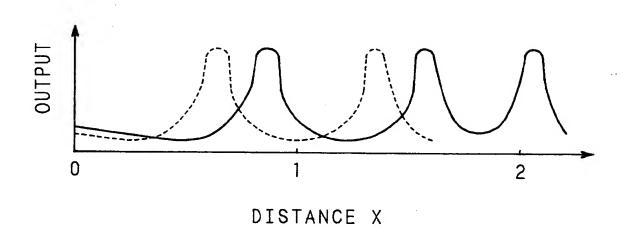
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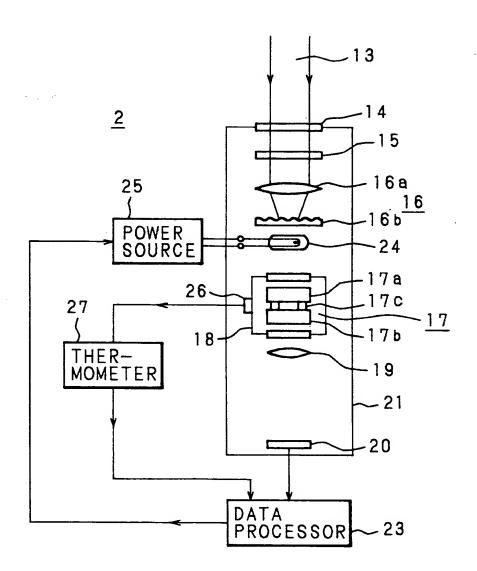


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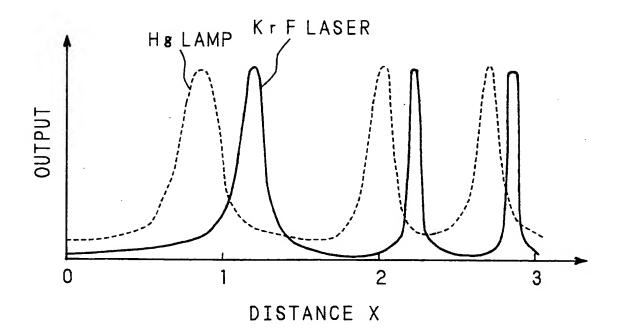
Fig. 2 Prior Art



F i g. 3



F i g. 4





EUROPEAN SEARCH REPORT

Application Number

EP 93 30 3755

Category	Citation of document with in		Relevant to claim	CLASSIFICATION OF THE APPLICATION (Int. Cl.5)
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O, X	GB-A-2 210 496 (MISI KAISHA)	DRIZHI DENKI KAROZHI	KI 1-5	H01S3/139 G01J9/02
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	The present search report has t	een drawn up for all claims		
	Place of search	Date of completion of the se	erch erch	Examiner
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	CATEGORY OF CITED DOCUME	E : earlier p	principle underlying stent document, but	g the invention published on, or
X: particularly relevant if taken alone Y: particularly relevant if combined with another document of the same category		other D : documen	after the filing date D: document cited in the application L: document cited for other reasons	
A : technological background O : non-written disclosure			& : member of the same patent family, corresponding	
P: intermediate document			document	